

ABSTRACT OF THE DISCLOSURE

A megasonic cleaning vessel for cleaning a semiconductor wafer, includes a top chamber wall; a bottom chamber wall; side walls extending between the top chamber wall and the bottom chamber wall forming a cleaning chamber; a megasonic transducer is provided in the cleaning chamber; a pedestal extends
5 upwardly from the bottom chamber wall for supporting the semiconductor wafer; and an electrical conduit is provided through the cleaning vessel for connecting an electrical cable to the megasonic transducer at atmospheric pressure.